

Notice of References Cited	Application/Control No. 10/595,640		Applicant(s)/Patent Under Reexamination TSUBATA ET AL.	
	Examiner EARL N. TAYLOR		Art Unit 2818	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-2005/0223986 A1	10-2005	Choi et al.	118/715
*	B	US-2002/0117691 A1	08-2002	Choi et al.	257/225
*	C	US-5,712,208	01-1998	Tseng et al.	438/770
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	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Wolf and Tauber; 6.5 Properties and Chemical Vapor Deposition of Silicon Nitride, Silicon Processing for the VLSI Era, Volume 1 - Process Technology Second Edition, 2000, pages 202-206
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.